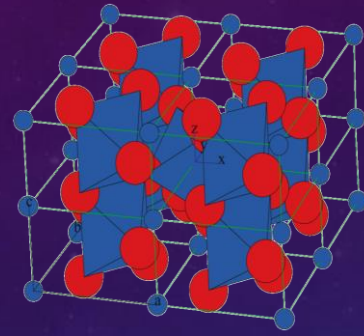




# HALL EFFECT ON VANADIUM OXIDES THIN FILMS



Speaker: Mileidy Varela

Graduate Seminar I  
Physics Department

There are some metal oxides that show a metal-insulator transition (MIT). Among those are vanadium oxides. Around a certain critical temperature ( $\text{VO}_2$  at  $T_{\text{MIT}} = 67^\circ\text{C}$ ) they present a phase transition accompanied by changes according to their stoichiometry in their structure, electrical, magnetic and optical behavior. Vanadium oxides, thanks to their good IR (infrared) absorption characteristics and manufacturing compatibility, can be used in information screens, variable reflector mirrors, smart windows, energy emission surfaces, memory devices and temperature sensors.



# Hall Effect on Vanadium Oxides Thin Films

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OCT-30-2018

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# Outline

- ▶ Hall Effect
  - Van der Pauw Technique
- ▶ Vanadium Oxides Films
  - Sputtering Reactive DC
- ▶ Previews Studies
- ▶ My proposal
- ▶ Conclusion



# Hall Effect

<https://www.youtube.com/watch?v=pEjzUqLAJAM>

LEARN  
AND  
GROW

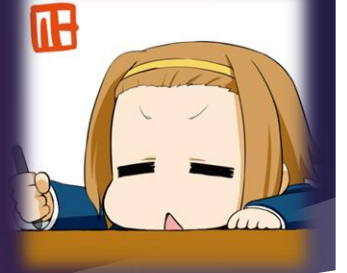
HALL EFFECT

LEARN  
AND  
GROW

- It is the voltage difference or electric field (named the **Hall** voltage) across an electrical conductor, transverse to an electric current in the conductor due to an applied magnetic field which is perpendicular to the current [1].

Fig 1. Hall Effect Diagram

# Hall Effect



► Lorentz Force:  $\vec{F} = q\vec{E} + q(\vec{v} \times \vec{B})$

$$\vec{F}_B = q\vec{v}_d \times \vec{B}$$

$$qv_d B = qE_H \quad E_H = v_d B$$

$$\text{area } A = td \quad v_d = \frac{I}{nqA}$$

$$\Delta V_H = E_H d = v_d B d$$

$$\Delta V_H = \frac{IBd}{nqA} = \frac{R_H IB}{t} \quad (1)$$

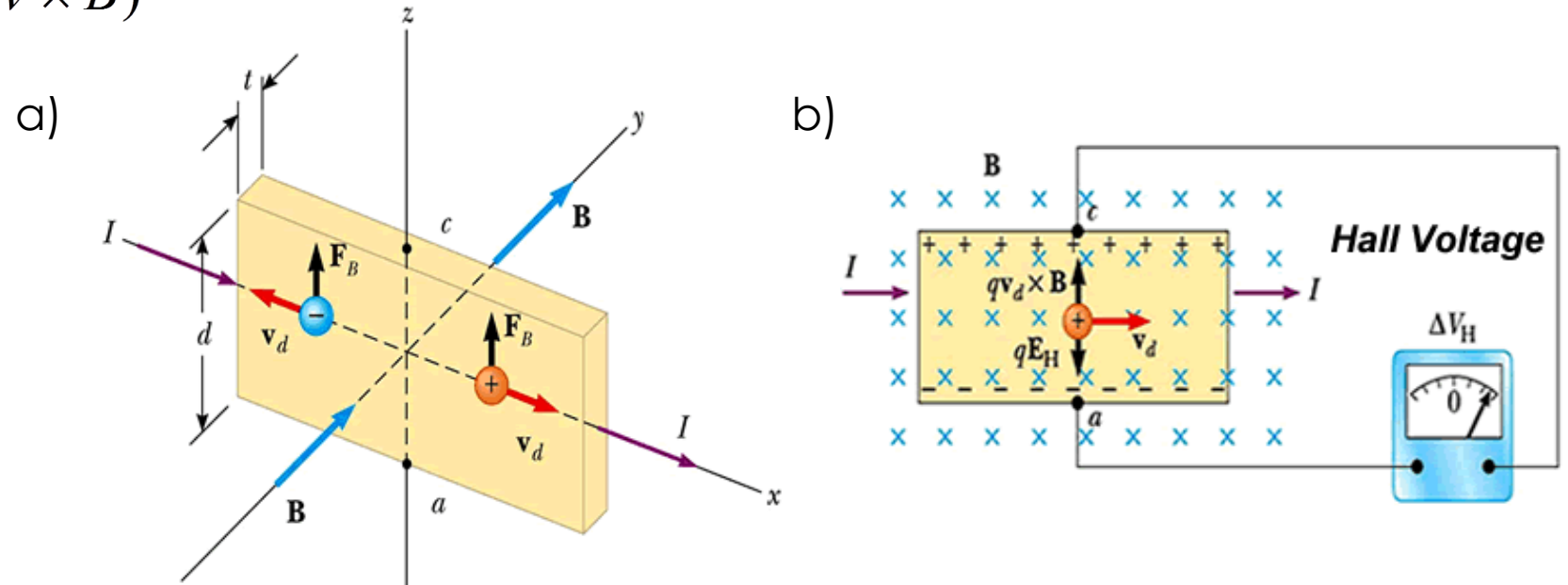


Fig 2. Representations of a) Lorentz Force and b) Hall Voltage

# Hall Effect

- ▶ This transverse voltage is the Hall voltage  $V_H$  and its magnitude is equal to.

$$V_H = IB/qnd \quad \mathbf{(2)}$$

- ▶ The sheet density  $n_s$  of charge carriers in semiconductors ( $n_s = nd$ ) as

$$n_s = IB/q |V_H| \quad \mathbf{(3)}$$

- ▶ Since sheet resistance involves both sheet density and mobility, the Hall mobility is

$$\mu = |V_H| / R_s IB = 1/(qn_s R_s) \quad \mathbf{(4)}$$



# Van der Pauw Technique

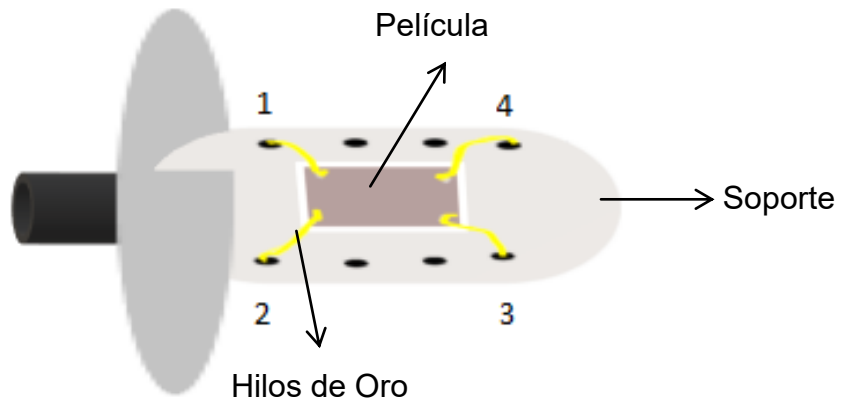


Fig 3. Van der Pauw experimental setup.

1. Have a uniform and flat thickness.
2. It must be homogeneous and isotropic.
3. It must not contain holes in it.
4. The four points should be located at the edges.
5. The area of this must be larger (an order of magnitude) than the contact area of any point.

# Van der Pauw Technique

- It uses an arbitrarily shaped, thin-plate sample containing four very small ohmic contacts placed on the periphery (preferably in the corners) of the plate.

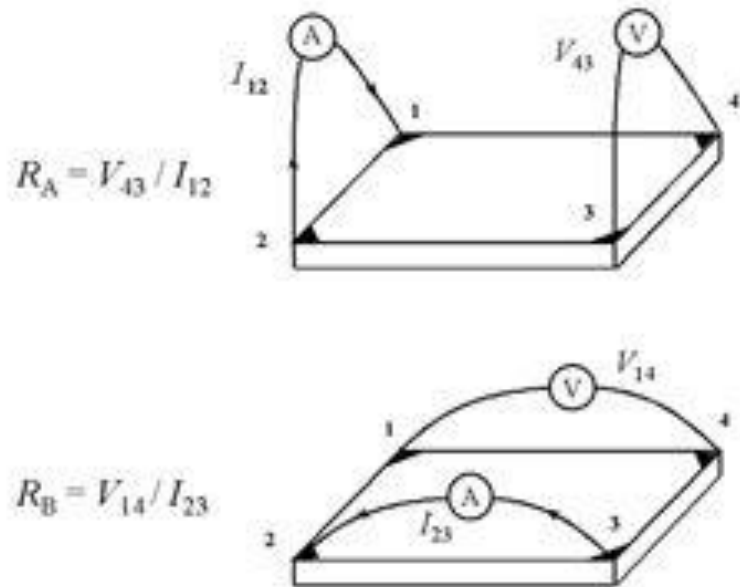


Fig 4. Resistance Measurements.

The Van der Pauw equation associate two characteristic resistances  $R_A$  and  $R_B$ , associated with  $R_s$ :

$$e^{\left(-\frac{\pi R_A}{R_s}\right)} + e^{\left(-\frac{\pi R_B}{R_s}\right)} = 1 \quad (5)$$

$R_A$  and  $R_B$  are calculated by means of the following expressions:

$$R_A = V_{43} / I_{12} \text{ and } R_B = V_{14} / I_{23}. \quad (6)$$



# Van der Pauw Technique – Hall Effect

- The objective of the Hall measurement in the van der Pauw technique is to determine the sheet carrier density  $n_s$  by measuring the Hall voltage  $V_H$ .

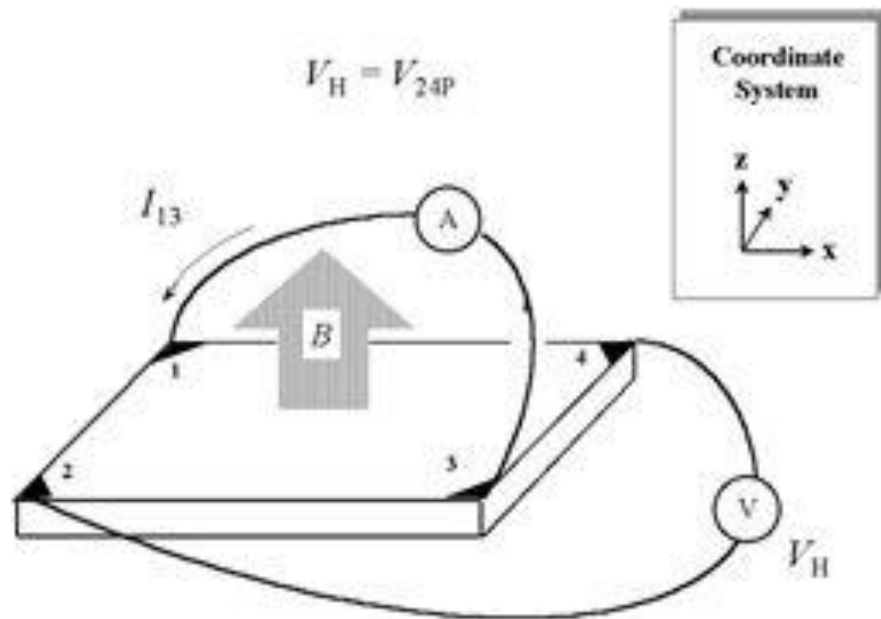


Fig 4.  $V_H$  Measurements.

To measure the Hall voltage  $V_H$ , a current  $I$  is forced through the opposing pair of contacts 1 and 3 and the Hall voltage is measured across the remaining pair of contacts 2 and 4.

$$V_H = V_{24} \quad (7)$$

# Vanadium Oxides Thin Films\*

- Vanadium oxides is among them in which a certain critical temperature present a metal-insulator phase transition accompanied by changes, according to their stoichiometry, in their structure and in their electrical, magnetic and optical behavior, becoming more attractive when they are studied.



50.9415 650.92 1.63	23
<b>V</b>	+5 +4 +3 +2 +1 -1 -3
<b>Vanadium</b>	
[Ar] 4s <sup>2</sup> 3d <sup>3</sup>	
Transition Metal	

15.9994 1313.95 3.44	8
<b>O</b>	+2 +1 -1 -2
<b>Oxygen</b>	
[He] 2s <sup>2</sup> 2p <sup>4</sup>	
Nonmetal	

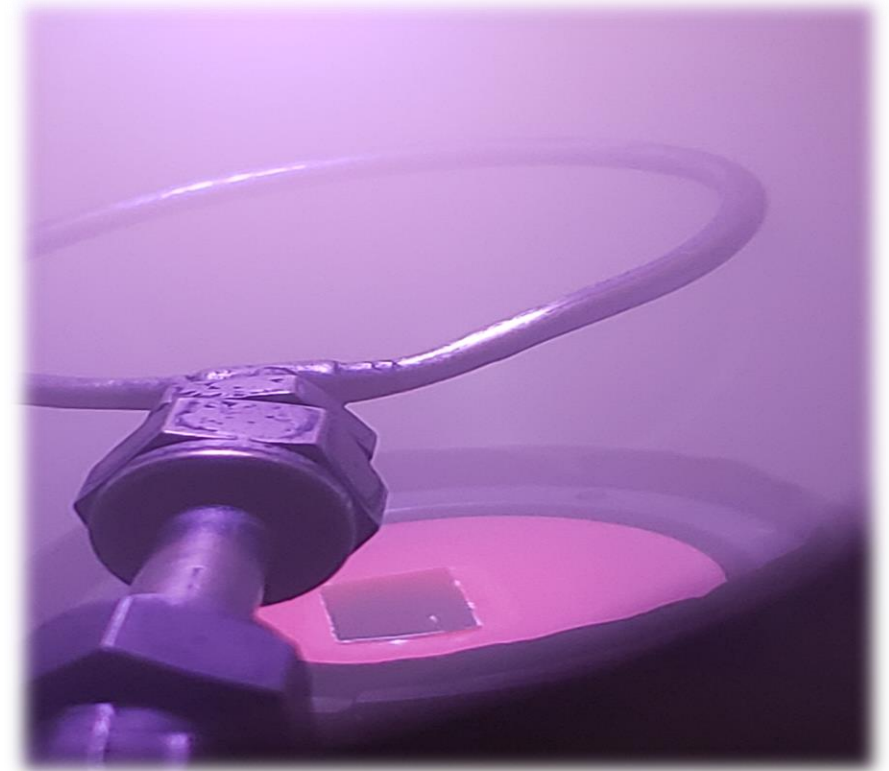


Fig 5. Deposition Sputtering for Vanadium Oxides.

\*A thin film is a layer of material ranging from fractions of a nanometer (monolayer) to several micrometers in thickness.

# Vanadium Oxides Thin Films - Applications

► The vanadium oxides can be used in:

- ✓ Information screens.
- ✓ Variable reflectivity mirrors.
- ✓ *Smart windows.* →
- ✓ Variable emittance surfaces [2,3].
- ✓ Memory devices.
- ✓ Thermometers.



Fig 6. Smart Windows.

# Vanadium Oxides Thin Films - Applications

- *Variable reflectivity mirrors:* They all switch from a metallic shiny state to an insulating transparent state.

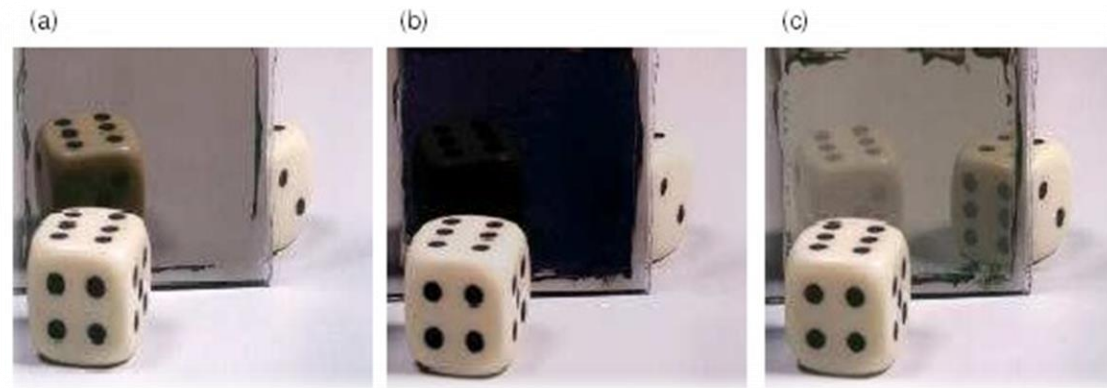


Fig 7. Variable reflectivity mirrors example.

# Vanadium Oxides Films

Vanadium-oxygen system could be around 14 different types of oxides formed from the oxidation states +2, +3, +4 and +5.

## Wadsley phase



where n values are between 1, 2 and 3

- Vanadium Dioxide ( $\text{VO}_2$ )

$$T_{\text{MIT}} \sim 340 \text{ K}$$

$\text{VO}_2$  thin film

Substrate ( $\text{SiO}_2$  /  $\text{Al}_2\text{O}_3$ )

## Magnéli phase



where n values are between 3, 4, 5... 9

- vanadium dioxide ( $\text{V}_4\text{O}_7$ )

$$T_{\text{MIT}} \sim 250 \text{ K}$$

$$T_{\text{Neel}} \sim 40 \text{ K}$$

# Magnetron Sputtering Reactive DC

- ▶ Sputtering refers to a method of physical vapor.
- ▶ The Sputtering system can use different types of power known as DC, pulsed DC and RF.
- ▶ In the DC reactive Sputtering magnetron the created plasma is magnetically confined near the surface of the substrate.

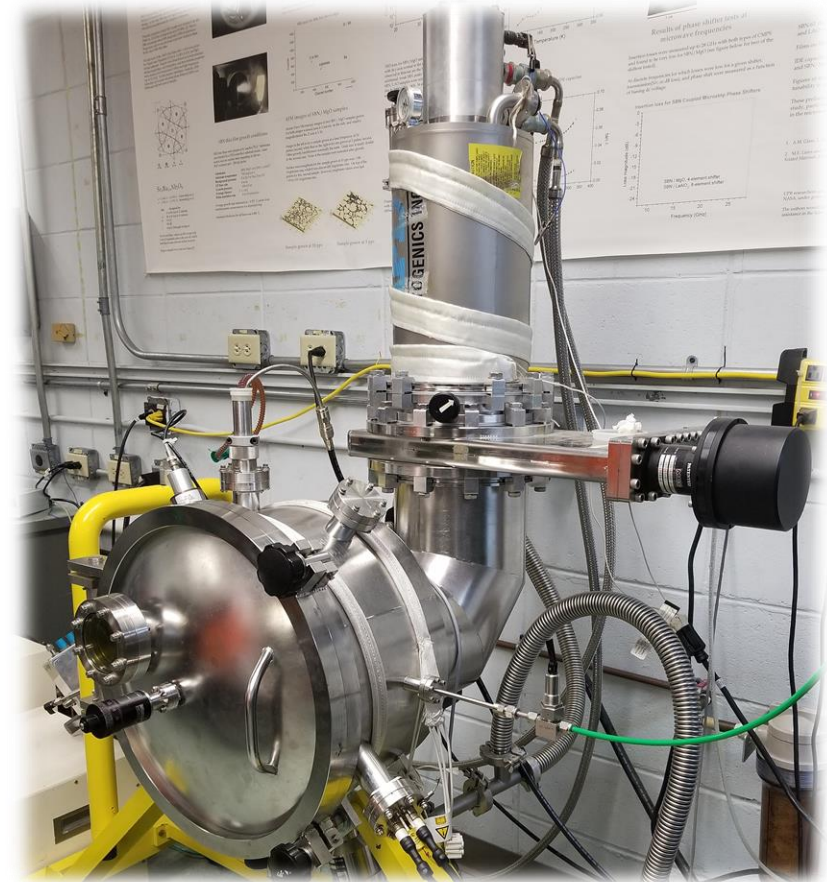


Fig 8. Sputtering system\*.



# Magnetron Reactive Sputtering DC

- The positively charged ions in the plasma are accelerated [4] by an electric field, and the target atoms are expelled or "pulverized" and then deposited on a substrate.

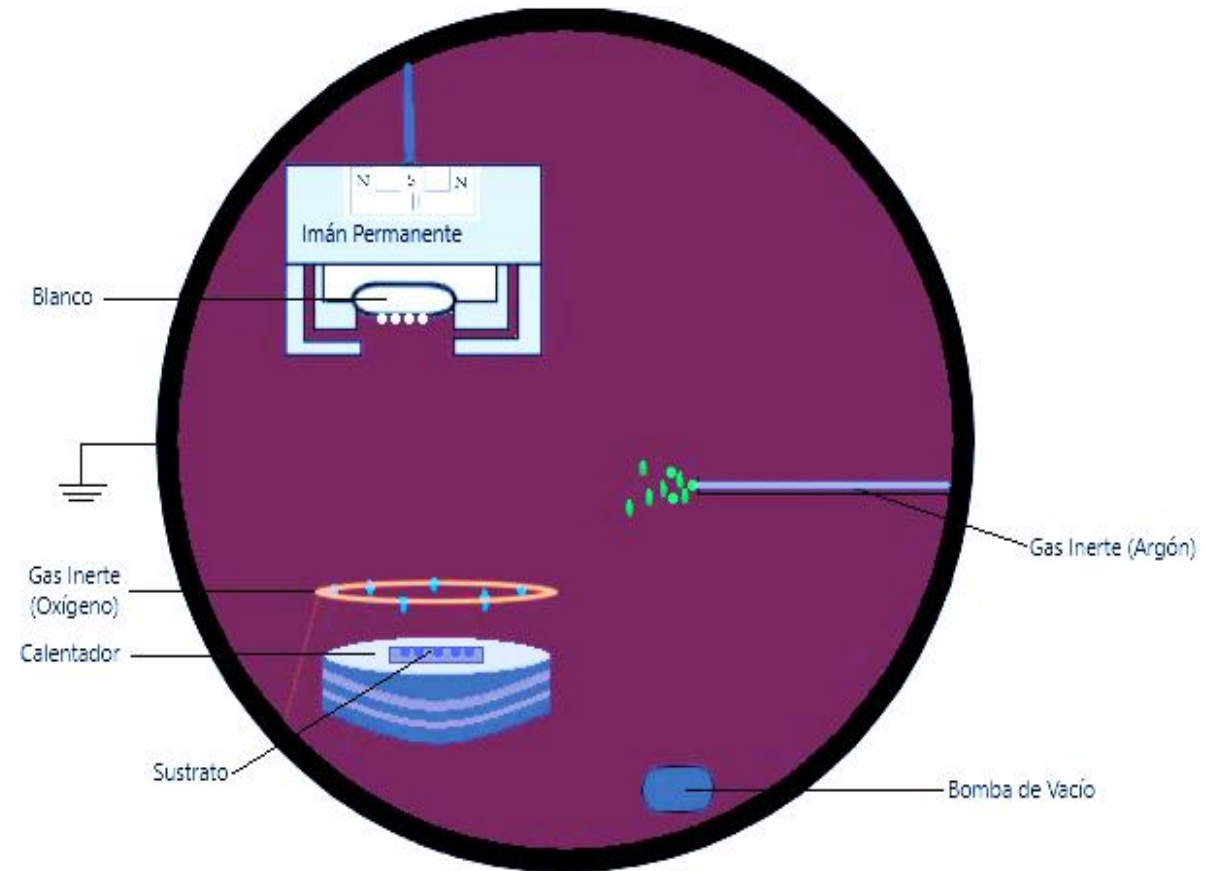
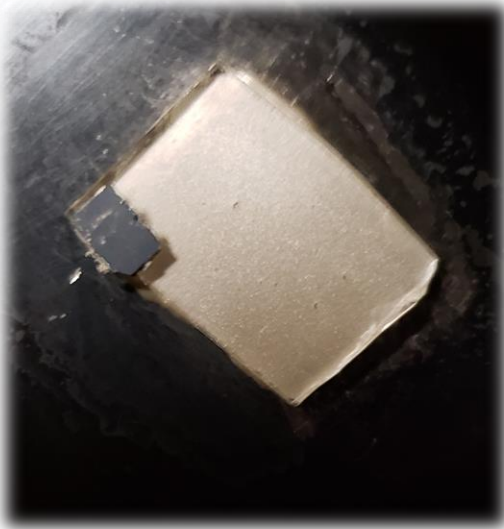


Fig 9. Sputtering diagram.



# Magnetron Sputtering Reactive DC

a)



b)



c)



Fig 10. Sputtering Process. a) Substrate in the heater . b) Pre-sputtering time. c) Sputtering time



# Magnetron Sputtering Reactive DC

Oxidation States	+5	+4	+3	+2
Oxides	$V_2O_5$	$VO_2$	$V_2O_3$	$VO$

a)

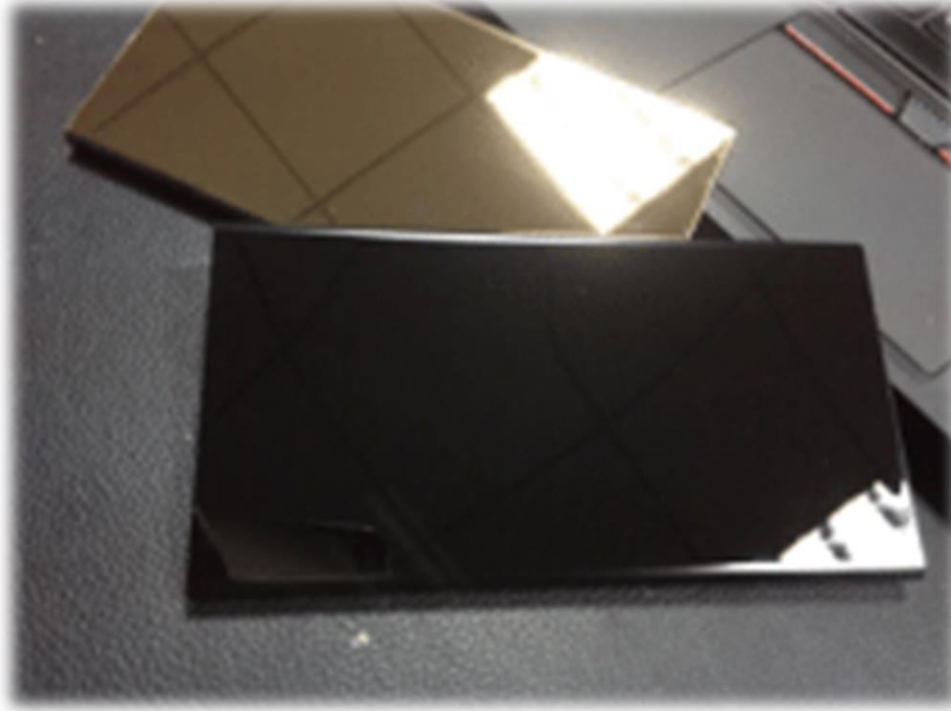


Fig 11. Thin Films Results.



# Previews Studies

► Hensler et. al [5]:

Carrier charge: (negative sign)  
Electrons.

Sample 2:  
 $V_H = 0.13 \text{ cm}^2/\text{V-sec}$  at  $300^\circ\text{K}$

Sample 6:  
 $V_H = 0.113 \text{ cm}^2/\text{V-sec}$  at  $363^\circ\text{K}$

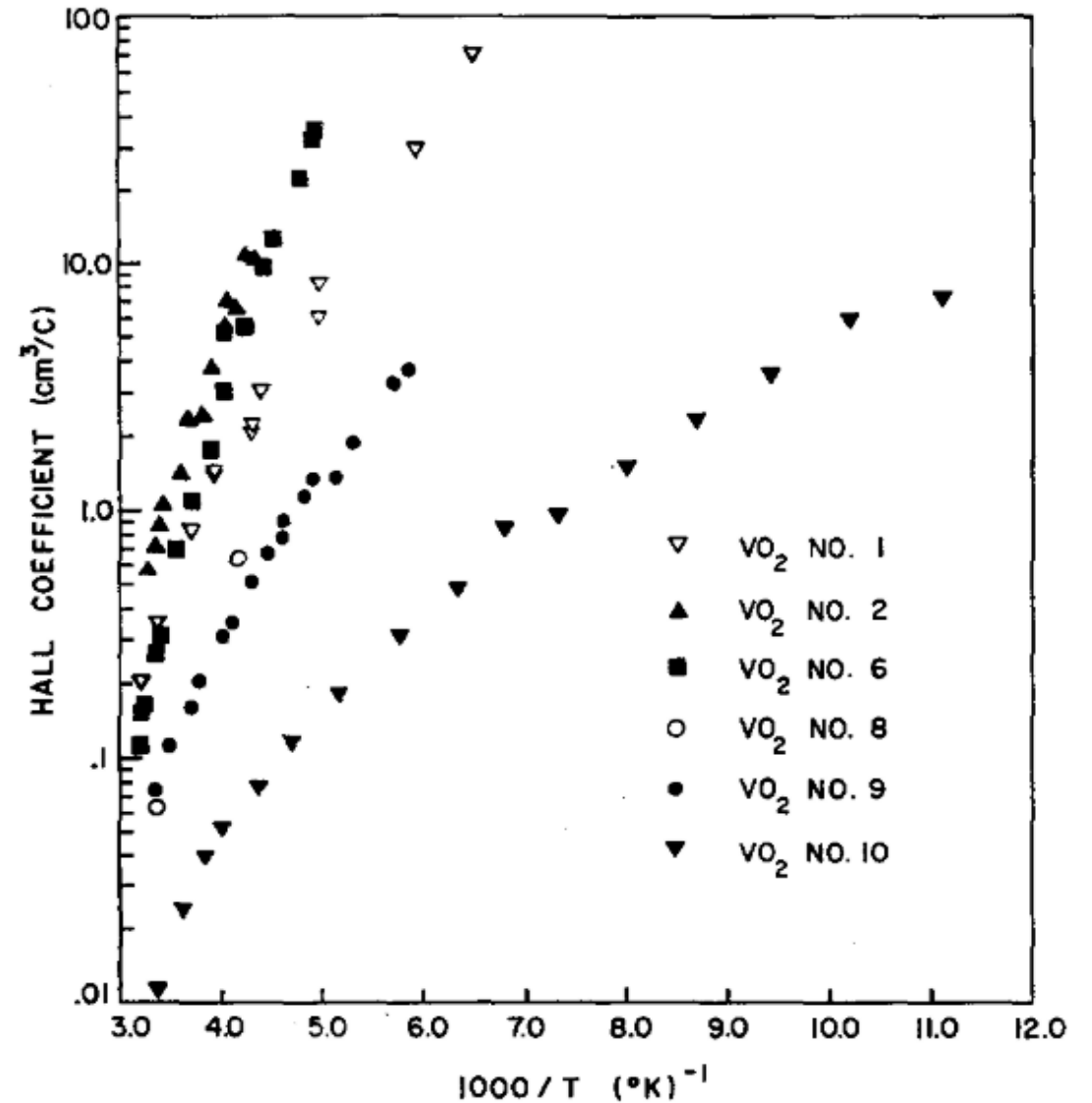


Fig 12. Hall coefficient vs reciprocal temperature substrate material.

# Previews Studies

► Ruzmetov et. al [6]:

Carrier charge: (negative sign)  
Electrons.

$V_H = 1.1 \times 10^{19} \text{ cm}^{-3}$  a  $64^\circ \text{C}$   
hasta  $1.7 \times 10^{23} \text{ cm}^{-3}$  a  $75^\circ \text{C}$ .

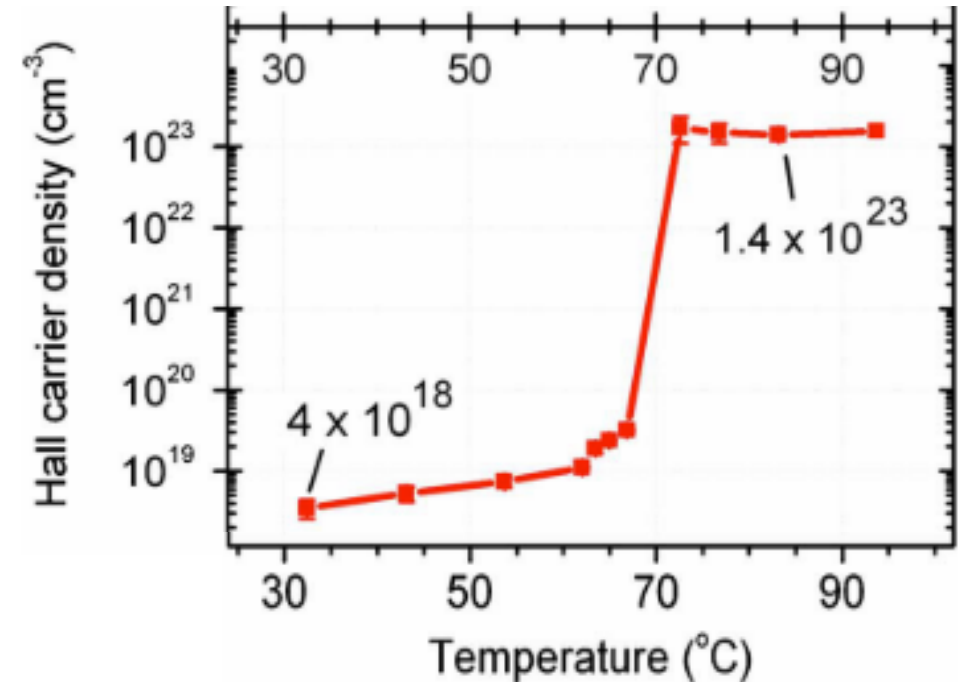


Fig 13. Electron transport properties of a thin film VO<sub>2</sub> on an Al<sub>2</sub>O<sub>3</sub> substrate (sample A) measured by 12 T sweeping field apparatus. The Hall-coefficient sign corresponds to electrons as the dominant current carriers.

# Previews Studies

► Song et. al [7]:

The sign of the Hall voltage is negative; thus electrons are the predominant carrier in both semiconducting and metallic phases.

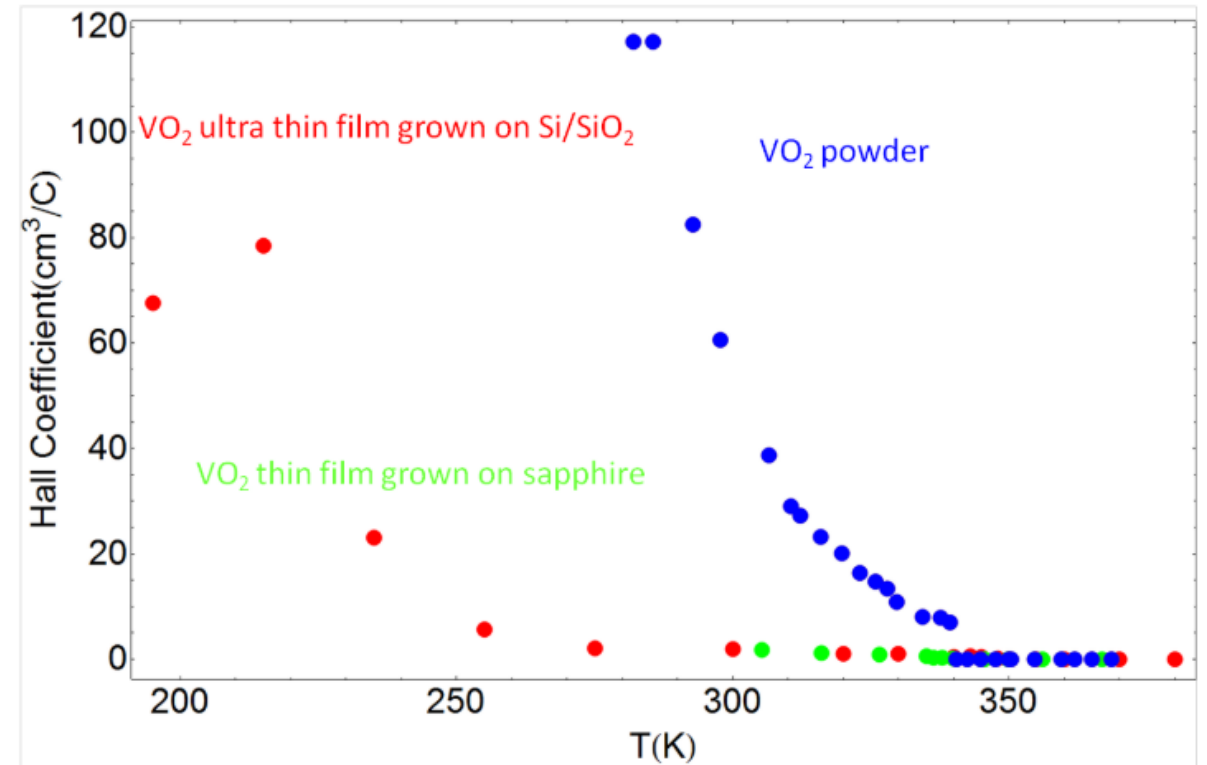


Fig 14. Temperature dependent hall coefficient.

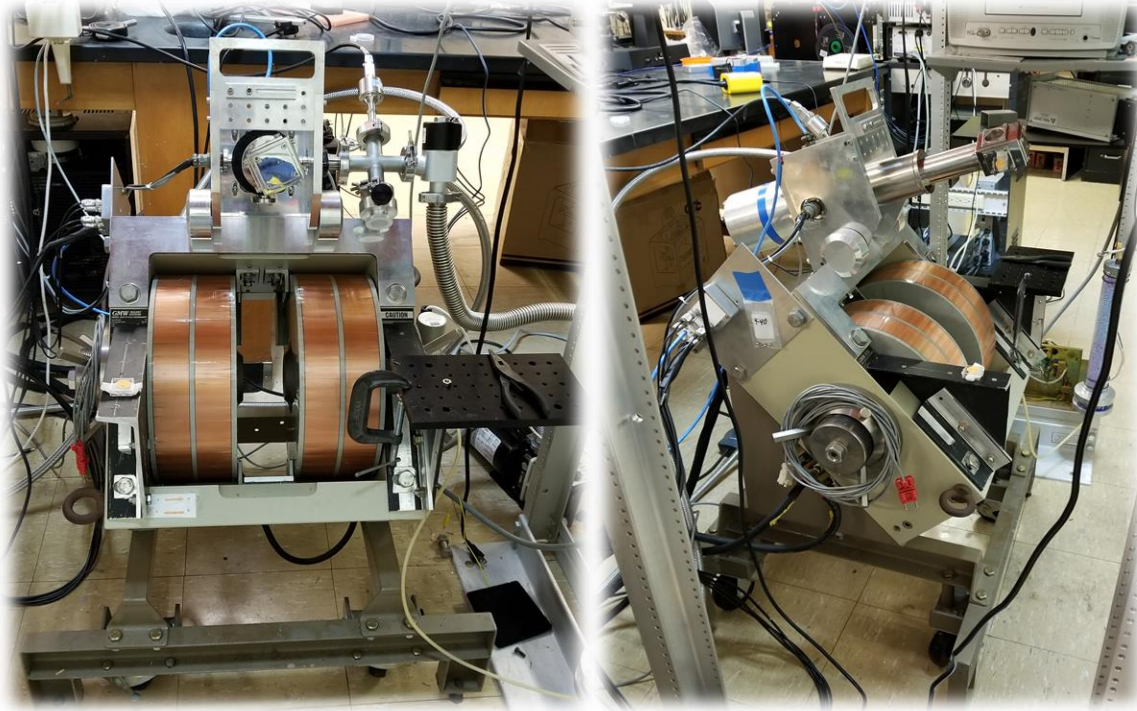
# My proposal

- Our main goal aims to grow vanadium oxides thin films as  $\text{VO}_2$  and  $\text{V}_4\text{O}_7$  and studies their magnetoresistance transport (properties) using the Hall effect taking advantage of the transitions that the material undergoes from metal to semiconductor since these occur at different temperatures.





# My proposal



**GMW MAGNET SYSTEMS**  
**MODEL 3472-70 ELECTROMAGNET**

Serial Number: 56  
Pole Diameter (max): 100 mm  
Pole Gap: 0 to 82 mm  
Coils (series connected):  
max resistance: 0.71 ohm  
max power (air): 20A/14V  
max power (water): 70A/50V  
Cooling Water (18 °C): 2.0 bar, 6 liter/min  
Thermal Interlock:  
resistive rating: 120Vac/0.5A  
closed below: 50 °C  
Water Flow Interlock:  
resistive rating: 120Vac/0.17A  
closed above: 4.5 liter/min  
Mass: 335 kg  
Field Direction: →

955 Industrial Rd, San Carlos, CA 94070  
Tel: (650) 802-8292, Fax: (650) 802-8298  
e-mail: sales@gmw.com web: www.gmw.com  
Made in New Zealand 10900 760



Fig 15. Hall equipment. (Resistivity Lab)



# Preliminary Data

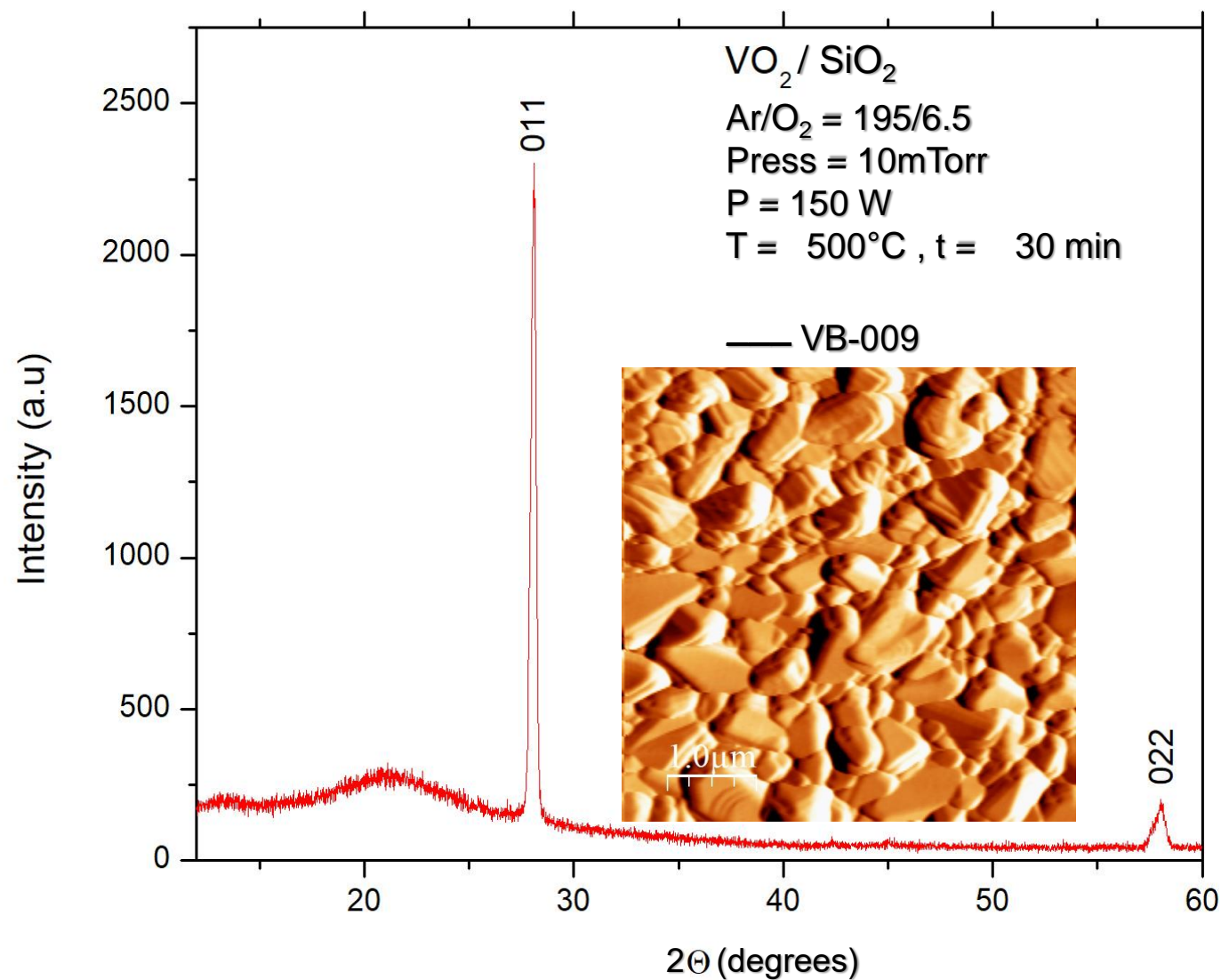


Fig 16. X-ray diffractogram and AFM results of VO<sub>2</sub>.

# Conclusion

- ▶ Hall effect: It is voltage difference transversal to an electric current in a conductor due to perpendicular applied magnetic field.
- ▶ Van der Pauwn Technique: It is a method that could measure resistivity with a great precision.
- ▶ Vanadium oxides are metal-insulator materials that present a transition in a certain temperature accompanied by changes their properties, specially in their electrical properties.
- ▶ Using the Hall effect we are going to measure some electrical properties taking advantage of the transitions that the material undergoes from metal to semiconductor since these occur at different temperatures.

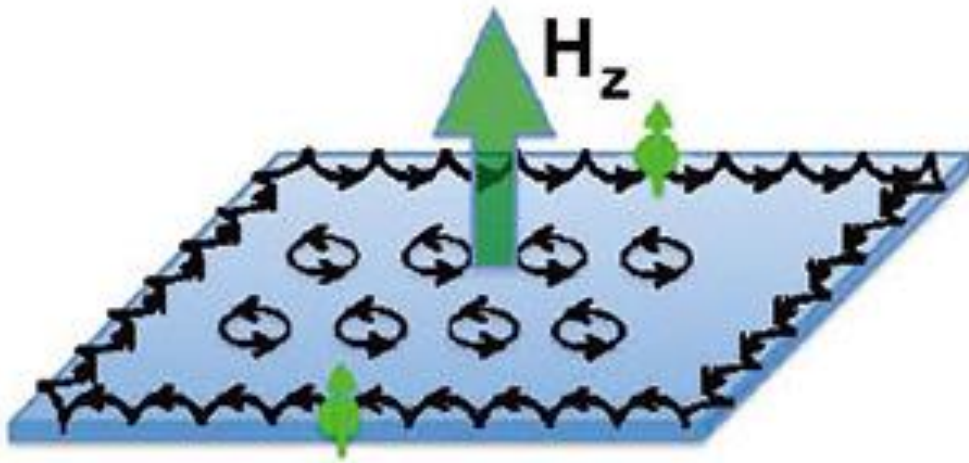
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Thanks



# Quantum Hall Effect



$$\sigma = \frac{I_{\text{channel}}}{V_{\text{Hall}}} = \nu \frac{e^2}{h} \quad (8)$$

The fractional quantum Hall effect is a variation of the classical Hall effect that occurs when a metal is exposed to a magnetic field. Classically, the Hall conductivity  $\sigma_{xy}$ —defined as the ratio of the electrical current to the induced transverse voltage—changes smoothly as the field strength increases. But in high-quality two-dimensional systems such as gallium arsenide quantum wells or graphene, the Hall conductivity instead features plateaus quantized at  $(8)$ , where  $e$  is the electron charge,  $h$  is Planck's constant, and  $\nu$  is a rational number.